

MATERIALS, COMPONENTS, AND METHODS FOR USE WITH EXTREME ULTRAVIOLET RADIATION IN LITHOGRAPHY AND OTHER APPLICATIONS

ABSTRACT OF THE DISCLOSURE

New classes of materials and associated components for use in devices and systems operating at ultraviolet (UV), extreme ultraviolet (EUV), and/or soft X-ray wavelengths are described. This invention relates to increasing the bandwidth and general performance of EUV reflective and transmissive materials. Such a material structure and combination may be used to make components such as mirrors, lenses or other optics, panels, light sources, photomasks, photoresists, or other components for use in applications such as lithography, wafer patterning, astronomical and space applications, biomedical applications, or other applications.